

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Masuda et al.

Appl. No. : 10/564,510

Filed : January 12, 2006

For : POSITIVE PHOTORESIST
COMPOSITION AND METHOD
OF FORMING RESIST PATTERN

Examiner : Chu, John S Y

Group Art Unit : 1752

OK TO ENTER: /JSC/

03/15/2008

RESPONSE TO OFFICE ACTION**Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **December 12, 2007**, please amend the above-referenced application as follows:

A **listing of claims** begins on page 2 of this paper for the Examiner's convenience. No amendments have been made

Remarks/Arguments begin on page 5 of this paper.